

EWS300

Microscopic Wafer Inspection



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Highlight:

With years of research and development, the EWS300 was developed based on the decade of experience in automation process resulting in the development of our state of art product, with the groundbreaking features that bring the product to a new level of simplicity, reliability and speed for automatic optical inspection solution.

SPECIFICATIONS

INSPECTION

Inspection Capabilities - Detecting wafer cosmetic defect, measurement, ink dot for wafer, probe mark & etc

Recipe / Setup (On and Off-Line) - Automatic "golden die" image generation from production wafer. Interactive graphical tools for

various zone definition. User-defined detection parameters per defects and zones.

Resolution - Changeable with multiple lens, up to 0.35μm per pixel

Accuracy - up to 0.7μm

- Represents deviation between average of the distribution of results of repeated measurements

of golden target and it certified value.

Repeatability - up to 0.7μm at 3 sigma

- Represents 3 sigma deviation value of the distribution of results of repeated measurements of

the same real component.

Minimum Defect Detection - up to 1µm

SYSTEM CONFIGURATION

Factory Automation - Secs/Gem
Cleanliness - Class 100/1000
Particles removal system - Hepa System

WAFER HANDLING

Wafer ID - Reading capability: SEMI M12, M13, M1.15, T1.95

- OCR

- ECC200, T7 DtaMatrix, QR-Code

- BC412, IBM412

Wafer Type - Wafer & Film Frame Wafer

Supported Wafer Size - 6", 8" & 12"

Wafer Cassettes - Standard Cassettes: Entegris, Empak or Fluoroware (FOUP Optional)

Wafer Handling - Twin Arms Wafer Robot with Slot Sensor (Mapping)

OUTPUT

Output Data - Wafer Map, SPC Analysis Report, KLARF

MACHINE LAYOUT

Dimension - L1620 x W2235 x H1950mm



